

Program Semicon Innovation Day

'Make it visible': focus on metrology

Science Centre, Mijnbouwstraat 120, Delft, The Netherlands, 21 May 2019

09:30	Registration
10:00	Welcome and opening Arnold Stokking, Managing Director TNO Industry
10:15	Keynote Talk: Metrology and Inspection challenges for Semicon High Volume Manufacturing Dr. Y.H. Sohn, M&I team, MTC, Memory Division, Samsung
10:45	Invited Talk: High throughput metrology solutions Hamed Sadeghian, CTO Nearfield Instruments
11:15	Advances in SPM tomography Paul van Neer, Senior Scientist, TNO
11:45	Photo thermal acoustic imaging Wouter Koek, Senior Scientist, TNO
12:15	Speakers corner topics 1 and 2
12:30	Lunch and poster sessions
13:45	Speakers corner topics 3, 4 and 5
14:00	Invited Talk: The Challenges of Defect Metrology in Advanced Technology Nodes Sigal Ben-Tzvi, Intel Corporation
14:30	Near-field detection techniques Giampiero Gerini, TNO, TU/e
14:45	Speakers corner: topics 6 and 7
15:00	Invited Talk: Advances in hybrid metrology Paul Hinnen, Program System Engineer Applications, ASML
15:30	Lab-on-an-instrument: concept and building blocks Teun van den Dool, Senior Scientist, TNO
16:00	Break and poster sessions
16:30	EUV beam line - 2: new results and future developments Norbert Koster, Principal Scientist, TNO
17:00	Cooperation TU/e TNO Henk Nijmeijer, TU/e
17:30	Speakers corner: 'What's next' and closure
17:45	Snacks and drinks

Speakers corner topics:

1. Overlay measurement tool | Stefan Kuiper, Senior System Architect, TNO
2. Bio-medical applications | Maurits van der Heiden, Senior System Architect, TNO
3. Contact hole/VIA manufacturing and measurement | Klará Maturová, Scientist, TNO
4. High throughput STED lithography | Arjen Boersma, Senior Scientist, TNO
5. Chemical imaging | Maarten van Es, Scientist, TNO
6. Artificial intelligence and defect detection | Maarten Kruihof, Scientist TNO
7. Quantum sensing | Clara Osorio Tamayo, Scientist, TNO